CORRECTED VERSION

(19) World Intellectual Property Organization

International Bureau





(43) International Publication Date 14 July 2005 (14.07.2005)

PCT

(10) International Publication Number WO 2005/063368 A3

B01F 5/00 (51) International Patent Classification7:

(21) International Application Number:

PCT/US2004/043152

(22) International Filing Date:

22 December 2004 (22.12.2004)

(25) Filing Language:

English

(26) Publication Language:

English

(30) Priority Data:

60/532,157

23 December 2003 (23.12.2003)

(63) Related by continuation (CON) or continuation-in-part (CIP) to earlier application:

US

60/532,157 (CON)

Filed on

23 December 2003 (23.12.2003)

- (71) Applicant (for all designated States except US): THE REGENTS OF THE UNIVERSITY OF MICHIGAN [US/US]; 3003 S. State Street, Ann Arbor, MI 48109 (US).
- (75) Inventors/Applicants (for US only): MEINERS, Jens-Christian [DE/US]; 8622 Warner Road, Saline, MI 48176 (US). CHEN, Hao [AR/US]; 2200 Fuller Court #811B, Ann Arbor, MI 48105 (US).
- (74) Agents: SYROWIK, David, R. et al.; Brooks Kushman, 1000 Town Center, Twenty-Second Floor, Southfield, MI 48075 (US).
- (81) Designated States (unless otherwise indicated, for every kind of national protection available): AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB. GD. GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE,

KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SM, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US (patent), UZ, VC, VN, YU, ZA, ZM, ZW.

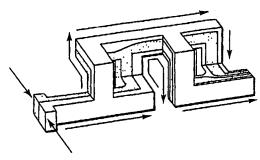
(84) Designated States (unless otherwise indicated, for every kind of regional protection available): ARIPO (BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW), Eurasian (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European (AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IS, IT, LT, LU, MC, NL, PL, PT, RO, SE, SI, SK, TR), OAPI (BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG).

Declarations under Rule 4.17:

- as to applicant's entitlement to apply for and be granted a patent (Rule 4.17(ii)) for the following designations AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA. CH. CN. CO. CR. CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SM, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, UZ, VC, VN, YU, ZA, ZM, ZW, ARIPO patent (BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW), Eurasian patent (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European patent (AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IS, IT, LT, LU, MC, NL, PL, PT, RO, SE, SI, SK, TR), OAPI patent (BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG)
- as to the applicant's entitlement to claim the priority of the earlier application (Rule 4.17(iii)) for the following designations AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW,

[Continued on next page]

(54) Title: METHOD FOR MIXING FLUID STREAMS, MICROFLUIDIC MIXER AND MICROFLUIDIC CHIP UTILIZING



(57) Abstract: A method for mixing fluid streams, microfluidic mixer and microfluidic chip utilizing same utilize a topological mixing scheme that exploits the laminarity of the flow to repeatedly fold the flow and exponentially increase the concentration gradients to obtain fast and efficient mixing by diffusion (Figure 1a). It is based on helical flow channels with opposite chiralities that split rotate and recombine the fluid stream in a topology reminiscent of a series of MÖBIUS bands. This geometry is realized in a simple six-stage, two-layer elastomer structure with a footprint of 400 µm x 300 µm per stage that mixes two solutions efficiently at Reynolds

numbers between 0.1 and 2. This represents more than an order of magnitude reduction in the size of microfluid mixers that can be manufactured in standard multilayer soft lithography techniques.

